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In the Claims:

- 1.(currently amended) A hard surface cleaner comprising a first precursor composition, being a thin alkaline liquid which contains a compound which generates chlorine dioxide under acidic conditions but not under alkaline conditions, and a second precursor composition, being a thin acidic liquid of pH not more than 5, and which comprises a mineral acid in aqueous solution, wherein on mixing the first and second precursor compositions the resulting admixed cleaning composition is acidic, causing the compound to generate chlorine dioxide, and is more viscous than the first precursor composition and more viscous than the second precursor composition.
- 2.(previously presented) A cleaning composition cleaner according to claim 1, wherein the viscosity of the first precursor composition is in the range 0.5-100 cps, the viscosity of the second precursor composition is in the range 0.5-100 cps and the viscosity of the cleaning composition produced by admixture thereof is 150-4000 cps.
- 3.(previously presented) A cleaning composition according to claim 1, wherein the first precursor composition is of pH at least 8, and comprises an alkali metal chlorite stabilized in aqueous solution by an additional base.
- 4.(canceled)
- 5.(previously presented) A cleaning composition according to claim 1, wherein the pH of the cleaning composition, formed by admixture of the first and second precursor compositions, is not more than 5.5

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- 6.(previously presented) A cleaning composition according to claim 1, wherein the first precursor composition and/or the second precursor composition contains a surfactant which thickens on admixture of the precursor compositions.
- 7.(previously presented) A cleaning composition according to claim 6, wherein the first precursor comprises such a surfactant, which thickens on admixture with acid.
- 8.(previously presented) A cleaning composition according to claim 6, wherein the surfactant is an anionic surfactant, being an alkyl sulphate or sulphonate.
- 9.(previously presented) A cleaning composition according to claim 6, wherein the surfactant is alkoxylated.
- 10.(previously presented) A cleaning composition according to claim 7, wherein the surfactant is a C₈₋₂₀ alkyl-EO₁₋₄ sulphate, with an alkali metal cation.
- 11.(previously presented) A cleaning composition according to claim 1, wherein the first and/or second precursor composition comprises a colour change agent which cause a change in appearance on mixing of the precursor compositions.
- 12.(currently amended) A cleaning composition according to claim 1, being a hard surface cleaner which comprises (% w/w values stated with reference to the total cleaning composition):
- 0.02-2% w/w, of a compound which under acid conditions generates chlorine dioxide, provided substantially wholly via the first precursor liquid;
 - 0.5-5% w/w, of an alkali metal, alkoxylated C₈₋₂₀ alkyl sulphate surfactant which thickens on being acidified, provided partially or substantially wholly via the first precursor liquid;
 - 20-46% w/w, water, provided via the first precursor liquid;

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an alkali metal base, provided substantially wholly via the first precursor liquid, in an amount such as to make the pH thereof at least 12;

20-46% w/w, water, provided via the second precursor liquid;

~~an~~ a mineral acid, provided substantially wholly via the second precursor liquid, in an amount such as to make the pH thereof not more than 5 and the pH of the admixed cleaning composition not more than 0.5 higher than the pH of the second precursor liquid;

wherein the viscosity (as measured herein) of the first precursor liquid is in the range 0.1-100 cps, the viscosity of the second precursor liquid is in the range 0.1-100 cps, and the viscosity of the admixed composition is in the range 150-1400 cps.

- 13.(currently amended) A hard surface cleaning pack comprising a first chamber containing a first precursor composition, being a thin alkaline liquid which contains a compound which generates chlorine dioxide under acidic conditions but not under alkaline conditions, and a second chamber containing the second precursor composition, being a thin acidic liquid of pH not more than 5, and which comprises a mineral acid in aqueous solution, wherein the chambers are adapted for simultaneous, separate, dispensing of the first and second precursor compositions with downstream mixing thereof, wherein on mixing the first and second precursor compositions the resulting admixed cleaning composition is acidic, causing the compound to generate chlorine dioxide, and is more viscous than both first precursor compositions.
- 14.(previously presented) A method of cleaning a hard surface, the method comprising use of a cleaning composition according to claim 1 which is an in situ mixture of the first precursor composition and the second precursor composition.
- 15.(original) A method as claimed in claim 14, comprising the admixture of the first and second precursor compositions, the first precursor composition constituting

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30-70 parts by weight of the cleaning composition and the second precursor composition constituting the balance.

16. (canceled)

17.(previously presented) A cleaning composition according to claim 12 being a hard surface cleaner which comprises (% w/w values stated with reference to the total cleaning composition):

0.1-1% w/w, of a compound which under acid conditions generates chlorine dioxide, provided substantially wholly via the first precursor liquid;

1.5-4% w/w, of an alkali metal, alkoxyated C₈₋₂₀ alkyl sulphate surfactant which thickens on being acidified, provided partially or substantially wholly via the first precursor liquid;

28-40% w/w, water, provided via the first precursor liquid;

an alkali metal base, provided substantially wholly via the first precursor liquid, in an amount such as to make the pH thereof at least 12;

28-40% w/w, water, provided via the second precursor liquid;

an acid, provided substantially wholly via the second precursor liquid, in an amount such as to make the pH thereof not more than 5 and the pH of the admixed cleaning composition not more than 0.5 higher than the pH of the second precursor liquid;

wherein the viscosity (as measured herein) of the first precursor liquid is in the range 0.1-100 cps, the viscosity of the second precursor liquid is in the range 0.1-100 cps, and the viscosity of the admixed composition is in the range 150-1400 cps.

18.(previously presented) A cleaning composition according to claim 17

wherein the viscosity (as measured herein) of the first precursor liquid is in the range 1-10 cps, the viscosity of the second precursor liquid is in the range

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1-10 cps, and the viscosity of the admixed composition is in the range 150-1400
cps.

19.(previously presented) A cleaning composition according to claim 18
wherein the viscosity of the admixed composition is in the range 500-1000
cps.